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## **Compact H<sup>+</sup> ECR Ion Source with Pulse Gas Valve**

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Compact H<sup>+</sup> ECR Ion Source using permanent magnets is under development. A pulsed gas injection system, achieved by a fast piezo gas valve, can reduce the gas load to a vacuum evacuation system. This feature is suitable when the ion source is closely located to an RFQ. Use of permanent magnets reduces the size. Achieved performance will be presented.

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